

REPLACED SHEETS		SG
☒ Description	: paged 1-4, 7-9, 11, 12	
☐ Claim(s)	: paged to paged	
☐ Drawing(s)	: paged to paged	
☐ Abstract	: paged to paged	
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SHORT CHANNEL IGBT WITH IMPROVED FORWARD
VOLTAGE DROP AND IMPROVED SWITCHING POWER LOSS

FIELD OF THE INVENTION

5 The present invention relates to a process for the manufacture of IGBTs and the resulting structure. More specifically, the present invention relates to an IGBT with reduced channel length or deeper enhanced concentration region that improves $V_{CE,ON}$ and that improves switching power loss.

10 BACKGROUND OF THE INVENTION

15 Insulated gate bipolar transistors (IGBTs) are well known and a typical structure and process of manufacture is described in British Patent No. 2,243,952. The channel length in such devices is typically that produced by a channel drive in of boron having an implant dose of 6 E15 per cm^2 followed by a drive for approximately 120 minutes, and followed again by an arsenic source implanted at 3 E15 per cm^2 and driven in at about 975°C.

20 This process has produced commercially acceptable IGBT devices with given forward voltage drops and switching power losses. Such devices are made by the International Rectifier Corporation of El Segundo, California.

25 It is always desirable to reduce the forward voltage drop of an IGBT and to decrease its switching power loss, namely to increase its safe operating area (SOA). It is also desirable to reduce the minority carrier lifetime ("lifetime killing") to increase the switching speed of the IGBT by reducing the lifetime of the minority carriers in the silicon. Though electron irradiation may be used to reduce minority carrier

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lifetime, the dose that can be irradiated into the IGBT must be less than 4 megarads to avoid "switchback" and is typically less than 3 megarads.

5 It is therefore desirable to provide a process which permits a substantial reduction in both forward voltage drop and SOA and allows electron irradiation at higher doses without switchback.

10 Moreover, the effect of the irradiation can be annealed out at die bond temperatures. The device must therefore be subsequently soldered at lower temperatures to avoid this annealing, which complicates the assembly process. Therefore, doping with a heavy metal, such as platinum or gold, is preferred for lifetime killing. However, heavy metal doping increases the apparent
15 resistivity in the active region between bases.

It is therefore also desirable to be able to use heavy metal doping in an IGBT without increasing forward voltage drop above that of a comparable electron irradiated IGBT.

20 BRIEF DESCRIPTION OF THE INVENTION

The present invention reduces the channel length of the channels of individual cells of a cellular IGBT by reducing the channel drive in time from the customary 120 minutes at 1175°C to between 60 and 90
25 minutes at 1175°C. The process also then permits the use of a higher minority carrier lifetime killing electron radiation dose of 4 megarads instead of the prior art 3 megarad to improve switching power loss while reducing SOA by only a small value. The device source is then
30 formed by an arsenic source implanted at 3 E15 followed by an anneal temperature greater than about 975°C. The new process reduces forward voltage drop or,



alternatively, switching speed by about 20%. The SOA is thus reduced by only 21 microseconds to 16 microseconds which is well within guaranteed withstand time for commercial IGBTs.

5 Alternatively, the present invention reduces forward voltage drop and switching loss by increasing the enhancement diffusion time to 12 hours and by reducing the channel drive in time from 2 hours to 1 hour. This process likewise permits the use of a higher lifetime
10 killing electron radiation dose of about 5 to 6 megarads for a 1200 volt IGBT device and of about 6.4 to 16 megarad dose for a 600 volt IGBT device. The process also permits the use of higher temperature lifetime killing platinum diffusion.

15 In accordance with the present invention, a power semiconductor device is manufactured by introducing carriers of a first conductivity type into the exposed surface of a thin semiconductor chip of the first conductivity type. The carriers are diffused to a first
20 depth into the substrate to form a region of increased concentration. A first mask layer having openings which overlie the region of increased conduction is formed, and a first given concentration of carriers of a second conductivity type opposite to that of the first
25 conductivity type is applied to the chip surface through the openings. A thin gate dielectric and a conductive gate electrode are formed over at least portions of the surface of the region of increased concentration. A second mask layer having openings is formed. The
30 openings surround and are at least adjacent to the locations of respective first mask layer openings and are bounded by respective areas of the thin gate dielectric. A second given concentration of carriers of the second



conductivity type, which is less than the first given concentration, is introduced through the second mask layer openings. The carriers of first and second given concentration are then diffused at about a temperature of 1175° C for a time ranging from 60 to 90 minutes. The carriers of the first given concentration form a body of relatively high concentration, and the carriers of the second given concentration channel region form a relatively low concentration channel region which surrounds the body of relatively high concentration and underlies the thin gate dielectric. A high concentration of carriers of the first conductivity type is introduced through the second mask opening and diffused to form shallow source regions. The shallow source regions diffuse laterally to underlie the thin gate dielectric and bound the inner edge of the low concentration channel. A source electrode is formed on the source regions as is a drain electrode which is electrically connected to the chip.

In accordance with this aspect of the present invention, a further mask layer may be formed prior to the step of introducing the carriers of the first conductivity type. The first mask layer has openings through which the carriers of the first conductivity type are introduced into the exposed surface of the chip.

The carriers of the first type that are introduced into the exposed surface of the chip may be diffused to a final depth which is reached by a diffusion at about 1175°C for about 12 hours.

The carrier lifetime of the chip may be reduced. The completed chip may be exposed to a radiation dose of about 4 megarads or a dose of about 5 to 16 megarads.



Heavy metal atoms may be diffused into the chip to kill carrier lifetime. The heavy metal atoms may be platinum atoms which are diffused at a temperature of about 955°C or at a temperature of about 960°C to 970°C.

5 The heavy metal atoms may alternatively be gold atoms.

Other features and advantages of the present invention will become apparent from the following description of the invention which refers to the accompanying drawings.

10 BRIEF DESCRIPTION OF THE DRAWINGS

The invention will now be described in greater detail in the following detailed description with reference to the drawings in which:

15 Figure 1 is a top view of the silicon surface of a cellular IGBT device;

Figure 2 is a cross-sectional view of Figure 1 taken across the section line 2-2 and shows the active area of several cells of the cellular IGBT; and

20 Figure 3 shows an enlarged view of the channel area of one-half of one of the cells of Figure 2 for both a known device as well as according to the invention.

DETAILED DESCRIPTION OF THE DRAWINGS

Referring first to Figures 1 and 2, there is shown a portion of the active area of a typical IGBT device. Only a few of the large number of hexagonal cells in the IGBT device are shown. The IGBT device comprises a silicon wafer 10 having a P⁺ substrate 11, a thin N⁺ buffer layer 12, and N⁻ epitaxial junction receiving layer 13, a plurality of P type spaced bases 14, 15 and 16 which are preferably polygonal in topology and which contain respective annular source regions 17,

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18 and 19 respectively. The surface area between the outer periphery of each source 17, 18 and 19 and the outer periphery of respective bases 14, 15 and 16 respectively defines respective annular invertible channel areas.

The invertible channel areas are covered by a polygonal web of gate oxide 20 which is in turn covered by a polysilicon gate layer 21. The gate layer 21 is covered by a low temperature oxide ("LTO") insulation layer 22. An aluminum emitter contact 23 is then formed atop the LTO 22 and a collector contact 24 is connected to the bottom of substrate layer 11.

In known processes, such as that of the aforementioned British patent, the wafer 10 shown in Figure 2 has flat parallel upper and lower surfaces and has a substrate 11 of boron doped P+ material having a thickness for example of 15 mils. The P+ material is doped to a resistivity of, for example, less than about 0.02 ohm centimeter. A thin epitaxially grown N+ layer 12 is grown atop the P+ substrate 11. Region 12 could also be a region which is diffused into substrate 11 or could be formed by direct wafer bonding.

A second epitaxial layer which defines the main voltage blocking region of the device is the N- layer 13 into which all diffused junctions are formed and is typically doped with phosphorus.

The first processing step on the wafer 10 is the formation of a thin oxide layer (not shown) having a thickness of, for example, about 400 angstroms. A conventional photoresist is applied to the top surface of oxide layer and is patterned to a mesh-type pattern. The exposed portion of the thin oxide layer is then etched away and results in the formation of a plurality of

rectangular oxide islands. Phosphorus is then implanted into the silicon through the oxide window pattern using the photoresist to mask the implant of the atoms. As an example, the phosphorus implant is carried out at an
5 accelerating energy of about 120 kev and at a preferred dose of about 3 E12, though the dose can range between about 2 E12 and 7 E12. Alternatively, the oxide is not etched and the phosphorus is implanted at a higher energy through the thin oxide into the silicon.

10 As a further alternative, a uniform blanket implant of phosphorus is first applied to the bare silicon surface over the active regions of the die prior to the growth of the thin oxide.

15 After stripping the photoresist, the phosphorous implant is next driven deep below the surface of N- region 13 to form an ultra-deep N⁺ "enhancement" region 30. In the known processes, the initial ultra-deep N⁺ "enhancement" implant is followed by a very long drive time, typically about 8 hours.

20 In the next step in the process, an oxide layer is grown atop the surface of the wafer, and a photoresist layer is deposited atop and then appropriately patterned to define windows. The oxide and the underlying thin oxide are then etched through the spaced windows in the
25 photoresist to expose the silicon surface. Thereafter, the photoresist is removed and a heavy boron dose is implanted deep into the exposed silicon surface areas to form the deep central body portions of regions 14, 15 and 16 in Figure 2. As an example, the boron implant is
30 carried out at an acceleration voltage of about 50 kev with a dose of about 6 E15. Following the implant step, in the conventional process, there is a short initial



drive of the implant, typically in dry nitrogen plus 1% oxygen, to obtain an initial drive of 1-2 micrometers.

5 Thereafter, oxide segments are grown over the P+ regions 14, 15 and 16. The P+ regions are initially driven for a short depth to avoid a substantial depletion of the surface boron during the growth of these oxide segments. A photoresist layer is then deposited atop the surface and patterned to define a window pattern by which all oxide except that overlying the P+ regions 14, 15 and 10 16 is etched away. The photoresist layer is subsequently removed and a thin gate oxide layer 20 is grown over the fully exposed active area of the wafer.

 A polysilicon layer 21 is then deposited atop the wafer and a photoresist layer is deposited atop the polysilicon. The photoresist is then patterned according to another masking step forming openings and is used as a mask to etch the polysilicon, thus forming windows above the gate oxide layer 20. Thereafter, the gate oxide layer is etched which exposes the remaining polysilicon web and the surface of the silicon substrate, and boron 20 is implanted through the diffusion windows. The boron dose here is about E13 at 50 kev, much lower than that of the heavy boron dose. This boron dose, after diffusion, will merge with the higher-dose boron region and will 25 form a low concentration P- type channel region 14a, 15a and 16a which surround and are shallower than the P+ body portions 14, 15 and 16 produced from the higher concentration implants. These regions are then typically driven in for about 2 hours at 1175°C to reach a depth of 30 about 4.5 microns. Thus, lighter doped boron regions 14a, 15a and 16a, which are annular regions, are formed in Figure 2, though it is clear that where these regions



overlap the P+ regions 14, 15 and 16 they merge with one another.

5 The P(-) shallow "shelves" 14a, 15a and 16a, which surround deep P+ regions 14, 15 and 16 are lightly doped channel regions extending beneath the gate oxide.

10 It will be noted that, in each drive including the P- drive in, all junctions continue to move deeper. The N+ region 30 moves to a lesser degree, and P+ regions 14, 15 and 16 move to a somewhat larger degree. It is also known to those skilled in the art that as the diffusions drive deeper they also move laterally, whereby the shallow diffusions 14a, 15a and 16a ultimately diffuse under the gate oxide.

15 The surface is then appropriately de-glassed and arsenic atoms are implanted at, for example, 50 kev at a dose of 3 E15 and are driven in at a temperature of 975°C for approximately 120 minutes, for example, to form the annular N++ source regions 17, 18 and 19.

20 Thereafter, an interlayer silicon dioxide or LTO coating 22 is formed over the surface of the chip and is then coated with a photoresist layer which is photolithographically patterned to define a contact mask opening. The surface exposed through the openings in the photoresist is then appropriately etched to expose the
25 underlying inner peripheral portions of the N++ sources 17, 18 and 19 and the central body of the P+ regions 14, 15 and 16. After removing the photoresist, a subsequently deposited aluminum layer is then photolithographically patterned and etched to form source
30 and gate electrodes (not shown). The aluminum emitter electrode 23 is a continuous electrode, which electrically connects each cell in parallel and shorts



each of the P+ body regions and the inner periphery of their respective annular N++ source regions.

5 An amorphous silicon layer (not shown) is then deposited over the surface of the wafer which is photolithographically patterned and etched to expose appropriate emitter and gate pads. During this operation, the amorphous silicon may be etched with a suitable plasma etch. Thereafter, material is removed from the bottom of the P+ layer 11, and a suitable
10 collector electrode 24 is then attached to the bottom surface.

This known process produces a junction pattern as shown by the dotted lines in Figure 3. The junction pattern has a channel length is ℓ_1 , which is the distance
15 between the edges of the source 17 and base 14 at the surface of region 13.

In accordance with a first aspect of the present invention, the drive in of the P⁻ channel regions is reduced from 120 minutes at 1175°C to a range of 60 to
20 90 minutes at 1175°C, and preferably about 90 minutes, which provides a smaller channel length ℓ_2 , shown in Figure 3, resulting from the reduced lateral diffusion of the P⁻ diffusion 14a, 15a and 16a.

The wafer is then subjected to lifetime killing
25 by either electron irradiation or by heavy metal diffusion. For example, platinum lifetime killing can be used by diffusing platinum into the silicon wafer at from 960°C to 970°C. Alternatively, in accordance with the invention, the wafer may be irradiated to a increased 4
30 megarad total dose.

The new process has been found to reduce forward voltage drop or, alternatively, switching speed, by about 20%. Thus, device SOA is reduced from about 21

microseconds to about 16 microseconds which is still within the guaranteed withstand time for commercial IGBTs.

5 Different source implant doses can be used for the N++ source regions 17, 18 and 19. Using a P⁻ channel implant of 8 E13 that is driven in for 90 minutes, the process has been tested for a group of 24 wafers. The test wafers were standard epitaxial wafers obtained from Sumitomo. The group was divided among two different
10 enhancement diffusion drive-ins, namely 8 hours and 12 hours, respectively. Three values of source implant doses were also tested, 3 E15, 6 E15 and 1 E16, respectively, and four furnace platinum drive-in temperatures of 905°C, 910°C, 915°C and 920°C,
15 respectively, were also tested. The tests produced the following results shown in Table I in which the reverse breakdown voltage BVD_{SS} , the threshold voltage V_{th} and the forward voltage drop V_{ON} for these split lot experiments are listed. It should be noted that wafers obtained from
20 other suppliers provide only slightly different results.

In accordance with another aspect of the present invention, the ultra-deep N⁺ "enhancement" region 30 is initially driven at a temperature of about 1175°C for about 12 hours, rather than the customary 8 hours,
25 and the low concentration P- type channel regions 14a, 15a and 16a are driven in at 1175 °C is reduced from 120 minutes to 60 minutes, resulting in a shorter channel length.

The shorter channel length, when combined with
30 the deeper enhancement region, allows for even higher lifetime killing electron radiation doses of up to 5 to 6 megarads without switchback for a 1200 volt IGBT device



and doses of about 6.4 to 16 megarads for a 600 volt IGBT device.

5 It has also been found that heavy metal doping, such as platinum diffused in at 955 °C for 10 minutes, may also be used to kill lifetime in place of irradiation while attaining acceptable forward voltage drops.

10 The process also reduces the blocking voltage by about 40 volts. It was found, however, that because of variation in the epitaxial layer thickness in the supplied wafers, this reduced blocking voltage occasionally resulted in devices that did not meet the 1200 volt specification. As a result, wafers having thicker epitaxial layers are required for this process.

15 Although the present invention has been described in relation to particular embodiments thereof, many other variations and modifications and other uses will become apparent to those skilled in the art. It is preferred, therefore, that the present invention be limited not by the specific disclosure herein, but only
20 by the appended claims.

TABLE I

HRS ENHANC. DRIVE	SOURCE IMPLANT DOSE	WAFER DATA				
		WAFER	FURN PT° C.	BVDss	Vth	20 AMPS Von
8 HRS	3 E15	1	SLOW	1220	3.2	1.55
	3 E15	2	905	MIA	MIA	MIA
	3 E15	3	910	1220	3.6	2.55
	3 E15	4	915	1230	3.6	2.75
	3 E15	5	920	1240	3.7	2.75
	6 E15	6	905	1240	3.4	2.15
	6 E15	7	910	1230	3.3	2.35
	6 E15	8	915	1230	3.4	2.80
	6 E15	9	920	1240	3.45	3.00
	1 E16	10	905	1190	3.6	2.00
	1 E16	11	910	1180	3.25	2.10
	1 E16	12	915	1200	3.45	2.40
	1 E16	13	920	1230	3.4	2.30
	3 E15	14	905	1210	3.75	2.05
12 HRS	3 E15	15	910	1210	3.6	2.20
	3 E15	16	915	1200	3.6	2.25
	3 E15	17	920	1200	3.6	2.50
	6 E15	18	905	1200	3.3	1.90
	6 E15	19	910	1200	3.3	2.15
	6 E15	20	915	1200	3.45	2.25
	6 E15	21	920	1210	3.45	2.40
	1 E16	22	905	1200	3.3	1.90
	1 E16	23	910	1200	3.5	2.05
	1 E16	24	915	1240	3.4	2.40

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WHAT IS CLAIMED IS:

1. A method of manufacture of a power semiconductor device comprising the steps of:

introducing carriers of a first conductivity type into the exposed surface of a thin semiconductor chip which is
5 of the first conductivity type and diffusing said carriers to a first depth into said substrate to form a region of increased conduction;

forming a first mask layer having openings which overlie said region of increased conduction and applying a
10 first given concentration of carriers of a second conductivity type, which is of opposite conductivity type to said first conductivity type, to said chip surface through said openings;

forming a thin gate dielectric and a conductive gate electrode over at least portions of the surface of said region
15 of increased conduction;

forming a second mask layer having openings which surround and are at least adjacent to the locations of respective ones of said first mask layer openings and bounded by respective areas of said thin gate dielectric, and
20 introducing a second given concentration of carriers of the second conductivity type, which is less than said first given concentration, to said chip through said second mask layer openings;

diffusing said carriers of said first and second
25 given concentrations of said second conductivity type at about a temperature of 1,175 °C for a time ranging from 60 to 90 minutes, with said carriers of said first given concentration forming a body of relatively high concentration and said carriers of said second given concentration forming a
30 relatively low concentration channel region which surrounds



said body of relatively high concentration and underlies said thin gate dielectric;

introducing a high concentration of carriers of said first conductivity type through said second mask openings and
35 diffusing said carriers to form shallow source regions which diffuse laterally to underlie said thin gate dielectric and bound the inner edge of said low concentration channel region; and forming a source electrode on said source regions and a drain electrode which is electrically connected
40 to said chip.

2. The method of claim 1 further comprising the step of forming a further mask layer prior to said step of introducing carriers of said first conductivity type, said further mask layer having openings through which said carriers
5 of said first conductivity type are introduced into said exposed surface of said chip.

3. The method of claim 1, which includes the further step of reducing the carrier lifetime of said semiconductor chip.

4. The method of claim 1, in which said carriers of said first type which are introduced into said exposed surface of said chip are diffused to a final depth which is reached by a diffusion at about 1175°C for about 12 hours.

5. The method of claim 4, which includes the further step of reducing the carrier lifetime of said semiconductor chip.

6. The method of claim 1, wherein said completed chip is exposed to a radiation dose of about 4 megarads.



- 16 -

7. The method of claim 4, wherein said completed chip is exposed to a radiation dose of about 5 to 16 megarads.

8. The method of claim 1, which includes the further step of diffusing heavy metal atoms into said chip to kill carrier lifetime.

9. The method of claim 8 wherein said heavy metal atoms are platinum about which are diffused at a temperature of about 960°C to 970°C.

10. The method of claim 4, which includes the further step of diffusing heavy metal atoms into said chip to kill carrier lifetime.

11. The method of claim 10, wherein said heavy metal atoms are platinum atoms which are diffused at a temperature of about 955°C.

12. The method of claim 10, wherein said heavy metal atoms are gold atoms.

SHORT CHANNEL IGBT WITH IMPROVED FORWARD
VOLTAGE DROP AND IMPROVED SWITCHING POWER LOSS

ABSTRACT OF THE DISCLOSURE

A cellular insulated gate bipolar transistor ("IGBT") device has a reduced length of the channels of the individual cells that is formed by reducing the channel drive in time from the customary 120 minutes at 1175°C to between 60 and 90 minutes at 1175°C. The process also permits the use of a higher minority carrier lifetime killing electron radiation dose to improve switching power loss while reducing SOA by only a small value. Alternatively, the increased concentration region located in the active region between spaced bases is initially driven in at a temperature of about 1175°C for about 12 hours, rather than the customary 8 hours, and the channel drive in time is reduced from 120 minutes to 60 minutes. The shorter channel length, when combined with the deeper enhancement region, allows for higher lifetime electron irradiation doses or heavy metal diffusion temperatures.

Fig. 3

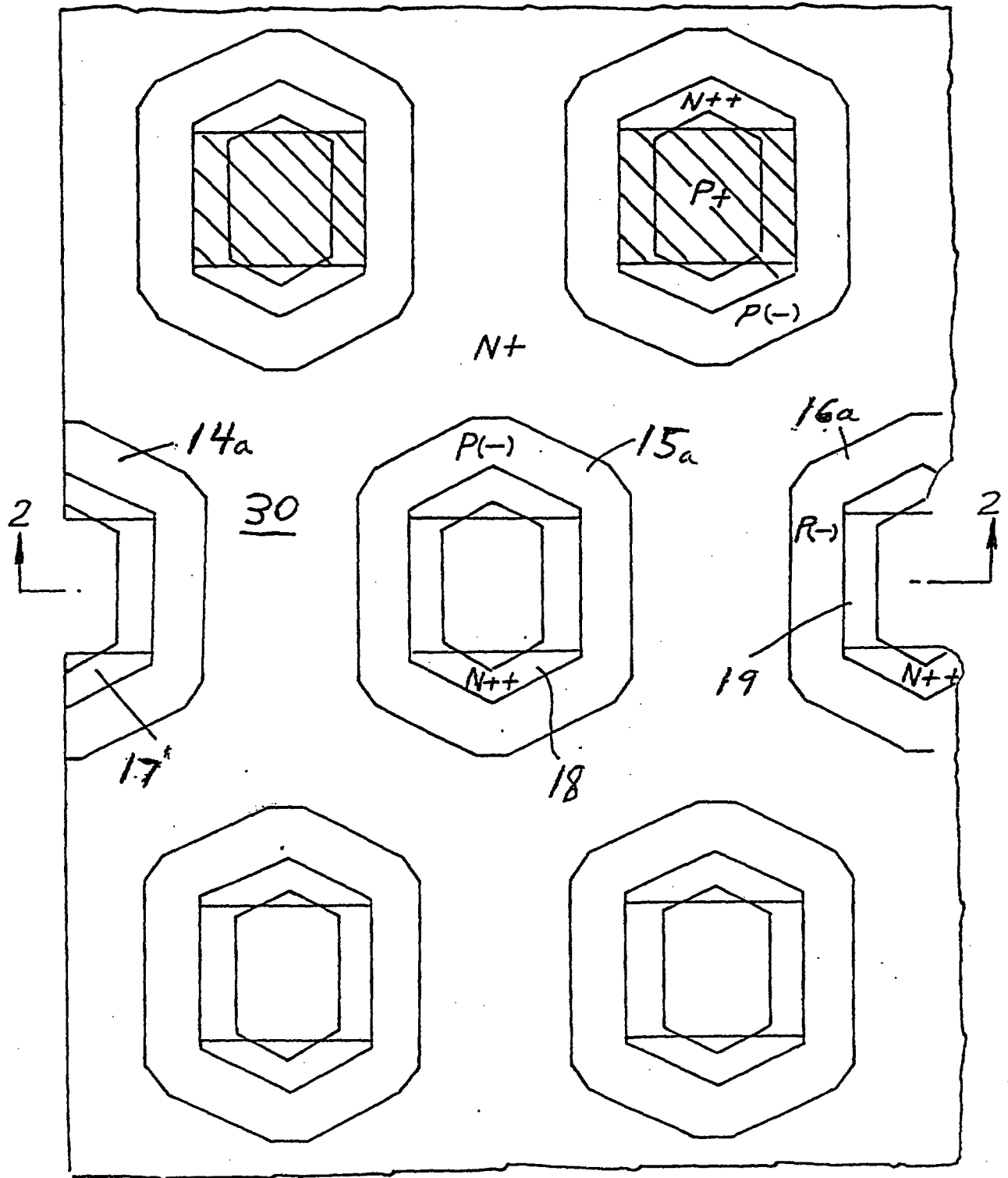
FIG. 1.

FIG. 2

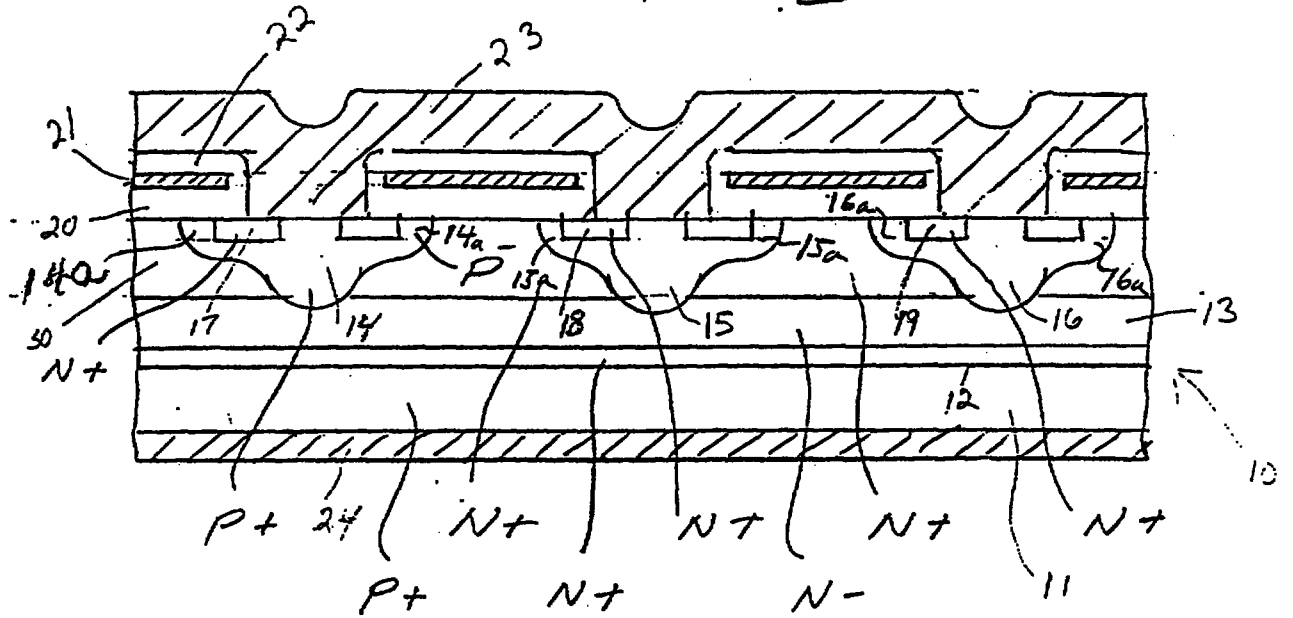
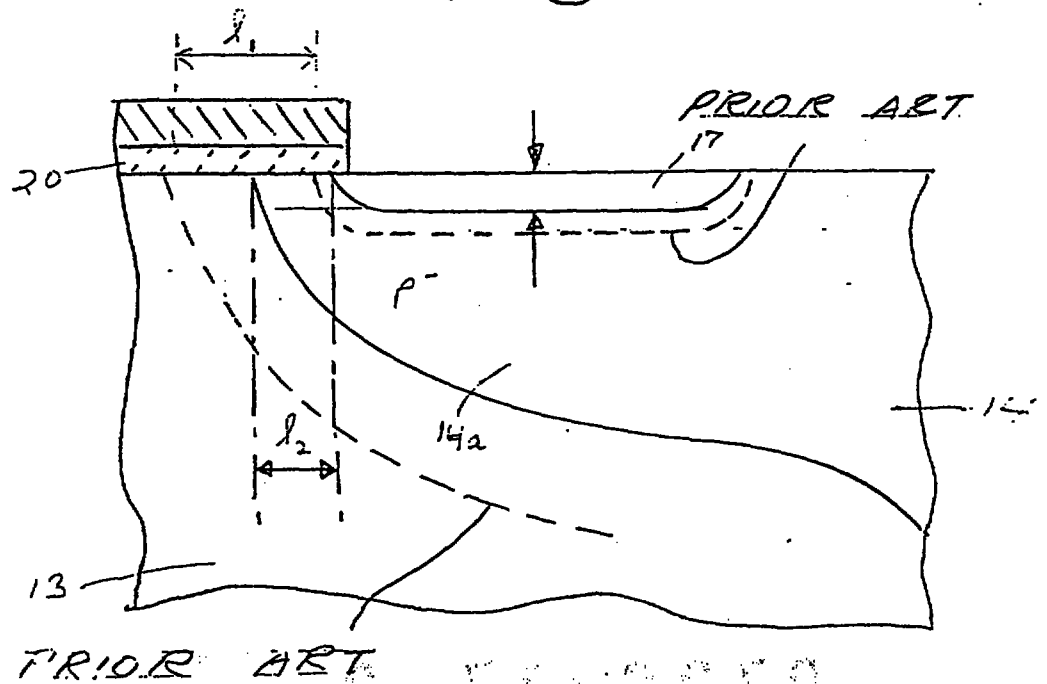
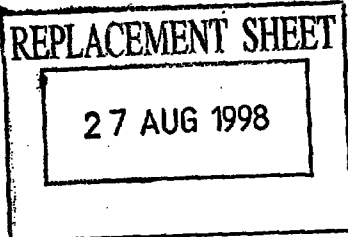
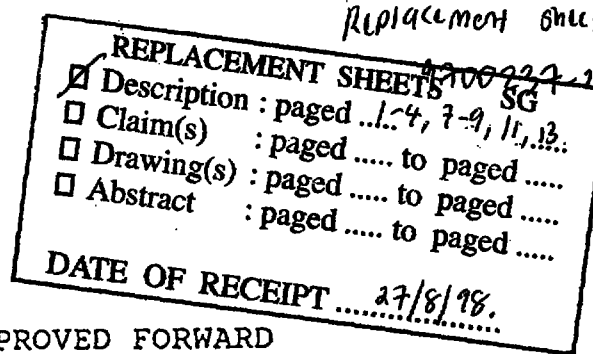


FIG. 3





- 1 -



SHORT CHANNEL IGBT WITH IMPROVED FORWARD
VOLTAGE DROP AND IMPROVED SWITCHING POWER LOSS

FIELD OF THE INVENTION

The present invention relates to a process for the manufacture of IGBTs and the resulting structure. More specifically, the present invention relates to an IGBT with reduced channel length or deeper enhanced concentration region that improves $V_{CE,ON}$ and that improves switching power loss.

BACKGROUND OF THE INVENTION

Insulated gate bipolar transistors (IGBTs) are well known and a typical structure and process of manufacture is described in British Patent No. 2,243,952. The channel length in such devices is typically that produced by a channel drive in of boron having an implant dose of 6 E15 per cm^2 (6×10^{15} atoms per cm^2) followed by a drive for approximately 120 minutes, and followed again by an arsenic source implanted at 3 E15 per cm^2 (3×10^{15} atoms per cm^2) and driven in at about 975°C .

This process has produced commercially acceptable IGBT devices with given forward voltage drops and switching power losses. Such devices are made by the International Rectifier Corporation of El Segundo, California.

It is always desirable to reduce the forward voltage drop of an IGBT and to decrease its switching power loss, namely to increase its safe operating area (SOA). It is also desirable to reduce the minority carrier lifetime ("lifetime killing") to increase the switching speed of the IGBT by reducing the lifetime of the minority carriers in the silicon. Though electron irradiation may be used to reduce minority carrier

27 AUG 1998

- 2 -

lifetime, the dose that can be irradiated into the IGBT must be less than 4 megarads to avoid "switchback" and is typically less than 3 megarads.

It is therefore desirable to provide a process which permits a substantial reduction in both forward voltage drop and SOA and allows electron irradiation at higher doses without switchback.

Moreover, the effect of the irradiation can be annealed out at die bond temperatures. The device must therefore be subsequently soldered at lower temperatures to avoid this annealing, which complicates the assembly process. Therefore, doping with a heavy metal, such as platinum or gold, is preferred for lifetime killing. However, heavy metal doping increases the apparent resistivity in the active region between bases.

It is therefore also desirable to be able to use heavy metal doping in an IGBT without increasing forward voltage drop above that of a comparable electron irradiated IGBT.

BRIEF DESCRIPTION OF THE INVENTION

The present invention reduces the channel length of the channels of individual cells of a cellular IGBT by reducing the channel drive in time from the customary 120 minutes at 1175°C to between 60 and 90 minutes at 1175°C. The process also then permits the use of a higher minority carrier lifetime killing electron radiation dose of 4 megarads instead of the prior art 3 megarad to improve switching power loss while reducing SOA by only a small value. The device source is then formed by an arsenic source implanted at 3×10^{15} atoms per cm^2 followed by an anneal temperature greater than about 975°C. The new process reduces forward voltage drop or,

REPLACEMENT SHEET
27 AUG 1998

- 3 -

alternatively, switching speed by about 20%. The SOA is thus reduced by only 21 microseconds to 16 microseconds which is well within guaranteed withstand time for commercial IGBTs.

Alternatively, the present invention reduces forward voltage drop and switching loss by increasing the enhancement diffusion time to 12 hours and by reducing the channel drive in time from 2 hours to 1 hour. This process likewise permits the use of a higher lifetime killing electron radiation dose of about 5 to 6 megarads for a 1200 volt IGBT device and of about 6.4 to 16 megarad dose for a 600 volt IGBT device. The process also permits the use of higher temperature lifetime killing platinum diffusion.

In accordance with the present invention, a method of manufacture of a power semiconductor device comprising the steps of:

- introducing carriers of a first conductivity type into the exposed surface of a thin semiconductor chip which is of the first conductivity type and diffusing said carriers to a first depth into said substrate to form a region of increased conduction;

- forming a first mask layer having openings which overlie said region of increased conduction and applying a first given concentration of carriers of a second conductivity type, which is of opposite conductivity type to said first conductivity type, to said chip surface through said openings;

- forming a thin gate dielectric and a conductive gate electrode over at least portions of the surface of said region of increased conduction;

- forming a second mask layer having openings which surround and are at least adjacent to the locations of respective ones of said first mask layer openings and bounded by respective areas of said thin gate dielectric, and introducing a second given concentration of carriers of the second conductivity type, which is less than said first

27 AUG 1998

- 4 -

given concentration, to said chip through said second mask layer openings;

diffusing said carriers of said first and second given concentrations of said second conductivity type at about a temperature of $1,175^{\circ}\text{C}$ for a time ranging from 60 to 90 minutes, with said carriers of said first given concentration forming a body of relatively high concentration and said carriers of said second given concentration forming a relatively low concentration channel region which surrounds said body of relatively high concentration and underlies said thin gate dielectric;

introducing a high concentration of carriers of said first conductivity type through said second mask openings and diffusing said carriers to form shallow source regions which diffuse laterally to underlie said thin gate dielectric and bound the inner edge of said low concentration channel region;

and forming a source electrode on said source regions and a drain electrode which is electrically connected to said chip.

In accordance with this aspect of the present invention, a further mask layer may be formed prior to the step of introducing the carriers of the first conductivity type. The first mask layer has openings through which the carriers of the first conductivity type are introduced into the exposed surface of the chip.

The carriers of the first type that are introduced into the exposed surface of the chip may be diffused to a final depth which is reached by a diffusion at about 1175°C for about 12 hours.

The carrier lifetime of the chip may be reduced. The completed chip may be exposed to a radiation dose of about 4 megarads or a dose of about 5 to 16 megarads.

27 AUG 1998

- 7 -

rectangular oxide islands. Phosphorus is then implanted into the silicon through the oxide window pattern using the photoresist to mask the implant of the atoms. As an example, the phosphorus implant is carried out at an accelerating energy of about 120 kev and at a preferred dose of about 3 E12 (3×10^{12} atoms per cm^2), though the dose can range between about 2 E12 (2×10^{12} atoms per cm^2) and 7 E12 (7×10^{12} atoms per cm^2). Alternatively, the oxide is not etched and the phosphorus is implanted at a higher energy through the thin oxide into the silicon.

As a further alternative, a uniform blanket implant of phosphorus is first applied to the bare silicon surface over the active regions of the die prior to the growth of the thin oxide.

After stripping the photoresist, the phosphorous implant is next driven deep below the surface of N- region 13 to form an ultra-deep N⁺ "enhancement" region 30. In the known processes, the initial ultra-deep N⁺ "enhancement" implant is followed by a very long drive time, typically about 8 hours.

In the next step in the process, an oxide layer is grown atop the surface of the wafer, and a photoresist layer is deposited atop and then appropriately patterned to define windows. The oxide and the underlying thin oxide are then etched through the spaced windows in the photoresist to expose the silicon surface. Thereafter, the photoresist is removed and a heavy boron dose is implanted deep into the exposed silicon surface areas to form the deep central body portions of regions 14, 15 and 16 in Figure 2. As an example, the boron implant is carried out at an acceleration voltage of about 50 kev with a dose of about 6 E15 (6×10^{15} atoms per cm^2). Following the implant step, in the conventional process, there is a short initial

27 AUG 1998

- 8 -

drive of the implant, typically in dry nitrogen plus 1% oxygen, to obtain an initial drive of 1-2 micrometers.

Thereafter, oxide segments are grown over the P+ regions 14, 15 and 16. The P+ regions are initially driven for a short depth to avoid a substantial depletion of the surface boron during the growth of these oxide segments. A photoresist layer is then deposited atop the surface and patterned to define a window pattern by which all oxide except that overlying the P+ regions 14, 15 and 16 is etched away. The photoresist layer is subsequently removed and a thin gate oxide layer 20 is grown over the fully exposed active area of the wafer.

A polysilicon layer 21 is then deposited atop the wafer and a photoresist layer is deposited atop the polysilicon. The photoresist is then patterned according to another masking step forming openings and is used as a mask to etch the polysilicon, thus forming windows above the gate oxide layer 20. Thereafter, the gate oxide layer is etched which exposes the remaining polysilicon web and the surface of the silicon substrate, and boron is implanted through the diffusion windows. The boron dose here is about E13 (10^{13} atoms per cm^2) at 50 kev, much lower than that of the heavy boron dose. This boron dose, after diffusion, will merge with the higher-dose boron region and will form a low concentration P- type channel region 14a, 15a and 16a which surround and are shallower than the P+ body portions 14, 15 and 16 produced from the higher concentration implants. These regions are then typically driven in for about 2 hours at 1175°C to reach a depth of about 4.5 microns. Thus, lighter doped boron regions 14a, 15a and 16a, which are annular regions, are formed in Figure 2, though it is clear that where these regions

27 AUG 1998

- 9 -

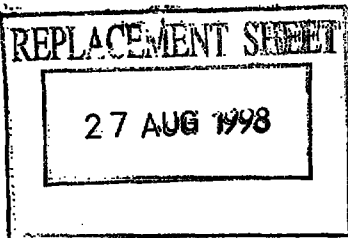
overlap the P+ regions 14, 15 and 16 they merge with one another.

The P(-) shallow "shelves" 14a, 15a and 16a, which surround deep P+ regions 14, 15 and 16 are lightly doped channel regions extending beneath the gate oxide.

It will be noted that, in each drive including the P- drive in, all junctions continue to move deeper. The N+ region 30 moves to a lesser degree, and P+ regions 14, 15 and 16 move to a somewhat larger degree. It is also known to those skilled in the art that as the diffusions drive deeper they also move laterally, whereby the shallow diffusions 14a, 15a and 16a ultimately diffuse under the gate oxide.

The surface is then appropriately de-glassed and arsenic atoms are implanted at, for example, 50 kev at a dose of 3×10^{15} atoms per cm^2 and are driven in at a temperature of 975°C for approximately 120 minutes, for example, to form the annular N++ source regions 17, 18 and 19.

Thereafter, an interlayer silicon dioxide or LTO coating 22 is formed over the surface of the chip and is then coated with a photoresist layer which is photolithographically patterned to define a contact mask opening. The surface exposed through the openings in the photoresist is then appropriately etched to expose the underlying inner peripheral portions of the N++ sources 17, 18 and 19 and the central body of the P+ regions 14, 15 and 16. After removing the photoresist, a subsequently deposited aluminum layer is then photolithographically patterned and etched to form source and gate electrodes (not shown). The aluminum emitter electrode 23 is a continuous electrode, which electrically connects each cell in parallel and shorts



- 11 -

microseconds to about 16 microseconds which is still within the guaranteed withstand time for commercial IGBTs.

Different source implant doses can be used for the N++ source regions 17, 18 and 19. Using a P channel implant of 8 E13 (8×10^{13} atoms per cm^2) that is driven in for 90 minutes, the process has been tested for a group of 24 wafers. The test wafers were standard epitaxial wafers obtained from Sumitomo. The group was divided among two different enhancement diffusion drive-ins, namely 8 hours and 12 hours, respectively. Three values of source implant doses were also tested, 3 E15 (3×10^{15} atoms per cm^2), 6 E15 (6×10^{15} atoms per cm^2) and 1 E16 (1×10^{16} atoms per cm^2), respectively, and four furnace platinum drive-in temperatures of 905°C, 910°C, 915°C and 920°C, respectively, were also tested. The tests produced the following results shown in Table I in which the reverse breakdown voltage BVD_{SS} , the threshold voltage V_{th} and the forward voltage drop V_{ON} for these split lot experiments are listed. It should be noted that wafers obtained from other suppliers provide only slightly different results.

In accordance with another aspect of the present invention, the ultra-deep N+ "enhancement" region 30 is initially driven at a temperature of about 1175°C for about 12 hours, rather than the customary 8 hours, and the low concentration P- type channel regions 14a, 15a and 16a are driven in at 1175 °C is reduced from 120 minutes to 60 minutes, resulting in a shorter channel length.

The shorter channel length, when combined with the deeper enhancement region, allows for even higher lifetime killing electron radiation doses of up to 5 to 6 megarads without switchback for a 1200 volt IGBT device

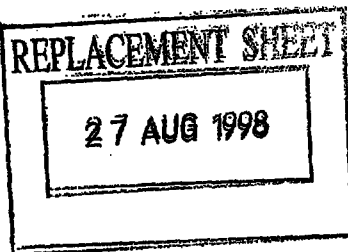


TABLE I

HRS ENHANC. DRIVE	SOURCE IMPLANT DOSE	WAFER DATA				
		WAFER	FURN PT° C.	BVDss	Vth	20 AMPS Von
8 HRS	3 E15	1	SLOW	1220	3.2	1.55
	3 E15	2	905	MIA	MIA	MIA
	3 E15	3	910	1220	3.6	2.55
	3 E15	4	915	1230	3.6	2.75
	3 E15	5	920	1240	3.7	2.75
	6 E15	6	905	1240	3.4	2.15
	6 E15	7	910	1230	3.3	2.35
	6 E15	8	915	1230	3.4	2.80
	6 E15	9	920	1240	3.45	3.00
	1 E16	10	905	1190	3.6	2.00
	1 E16	11	910	1180	3.25	2.10
	1 E16	12	915	1200	3.45	2.40
	1 E16	13	920	1230	3.4	2.30
12 HRS	3 E15	14	905	1210	3.75	2.05
	3 E15	15	910	1210	3.6	2.20
	3 E15	16	915	1200	3.6	2.25
	3 E15	17	920	1200	3.6	2.50
	6 E15	18	905	1200	3.3	1.90
	6 E15	19	910	1200	3.3	2.15
	6 E15	20	915	1200	3.45	2.25
	6 E15	21	920	1210	3.45	2.40
	1 E16	22	905	1200	3.3	1.90
	1 E16	23	910	1200	3.5	2.05
	1 E16	24	915	1240	3.4	2.40

where: "3 E15" is 3×10^{15} atoms per cm^2

"6 E15" is 6×10^{15} atoms per cm^2

"1 E16" is 1×10^{16} atoms per cm^2